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Claims 1-6, 9-29, 34-60, 62-67, and 70-76 are now pending. Claims 1-76 have been examined. Claims 8, 18-23, 30-33, 61 and 68-69 have been herein canceled without prejudice. Claims 1-6, 16-24, 28, 29, 34-42, 57-60, 62-68 and 70-75 have been rejected. Claims 8-15, 30-33, 61, 69 and 76 were objected to but would be allowable if written in independent form, including all limitations from its independent and intervening claims. Claims 25-27 and 43-56 have been allowed. Applicants appreciate this indication of allowability.

Independent claims 1 and 38 have been amended to include the limitation of allowable claim 8 reciting that "the etching solution oxidizes the metal of the substrate to a metal oxide". Independent claims 57 and 67 have been amended to include the limitation of allowable claims 61 and 69 to recite that "the etching solution comprises between about 0.05% and 15% glycine by weight and between about 0.5% and 20% peroxide by weight". Allowable dependent claim 30 was written in independent form including limitations of previously presented claim 1 that it depended from. Other claims have been amended to make minor clerical changes.

Claims 1-6, 16-24, 28-29, and 34-42 were rejected based on at least one of US Patent No. 6,355,153 issued to Uzoh et al., US Patent Application Publication No. 2003/003711A1 by Modak et al. and a US Patent No. 5,770,095 issued to Sasaki et al. Claims 57-60, 62-68 and 70-75 were rejected based on a combination of Sasaki as described above and a US Patent No. 6,184,124 issued to Hasegawa et al.

Rejections based on Uzoh, Modak, Sasaki and Hasegawa.

While Applicants believe that previously presented claims are patentable in view of the cited references, in order to expedite the issuance of a patent for the allowable subject matter, the Applicants have amended independent claims 1, 38, 57 and 67 to include the limitations of allowable dependent claims. Neither of the cited references teaches or suggests etching or deposition methods wherein the "etching solution oxidizes the metal of the substrate to a metal oxide" or wherein "the etching solution comprises between about 0.05% and 15% glycine by weight and between about 0.5% and 20% peroxide by weight". Withdrawal of the rejection is respectfully requested.

The Applicants herein reserve the right to introduce claims previously presented during prosecution of this patent application in a continuation or any other related application.

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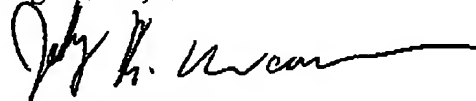
Conclusion

Applicants believe that all pending claims are allowable and respectfully request a Notice of Allowance for this application from the Examiner. Should the Examiner believe that a telephone conference would expedite the prosecution of this application, the undersigned can be reached at the telephone number set out below.

Respectfully submitted,
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